

	Hits	Search Text	DBs
1	0	((substrate or wafer) same (polyamic or polyimide) same (alicyclic near3 tetracarboxylic near5 dianhydride) same ((alicyclic or (divalent near4 hydrocarbon)) near4 diamine) same (heat\$4 or bak\$3 or anneal\$4)) and ((expos\$ or imaging or irradiat\$4 or illuminat\$4) same develop\$4 same pattern\$4) and ((dielectric or TiO or TiN or SiN) same first) and ((dielectric or TiN or SiN or TiO) same second) and (metal\$3 or conductive or wir\$3)	US - PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB
2	5	(("3699649") or ("4468414") or ("4594265") or ("6004734") or ("6365483")).PN.	US - PGPUB; USPAT
3	0	((substrate or wafer) same (polyamic or polyimide) same (alicyclic near3 tetracarboxylic near5 dianhydride) same ((alicyclic or (divalent near4 hydrocarbon)) near4 diamine)) and ((expos\$ or imaging or irradiat\$4 or illuminat\$4) same develop\$4 same pattern\$4) and ((dielectric or TiO or TiN or SiN) same first) and ((dielectric or TiN or SiN or TiO) same second) and (metal\$3 or conductive or wir\$3)	US - PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB
4	1	("20040132243").PN.	US - PGPUB; USPAT
5	1	((substrate or wafer) same (polyamic or polyimide) same (alicyclic near3 tetracarboxylic near5 dianhydride) same ((alicyclic or (divalent near4 hydrocarbon)) near4 diamine) same (heat\$4 or bak\$3 or anneal\$4)) and ((expos\$ or imaging or irradiat\$4 or illuminat\$4) same develop\$4 same pattern\$4)	US - PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB

	<b>Hits</b>	<b>Search Text</b>	<b>DBs</b>
6	478	((substrate or wafer) same (polymer\$2 or photoresist or resist) same (expos\$ or imaging or irradiat\$4 or illuminat\$4) same develop\$4 same pattern\$4) and ((dielectric or TiO or TiN or SiN) same first same second same (metal\$3 or wiring or conductive) same pattern) and ((remov\$3 or strip\$4) same (polymer\$3 or photoresist or resist) same pattern) and (metal\$3 or conductive or wir\$3)	US-PPGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB
7	33	((substrate or wafer) same (polyimide or polyamic) same (expos\$ or imaging or irradiat\$4 or illuminat\$4) same develop\$4 same pattern\$4) and ((dielectric or TiO or TiN or SiN) same first same second same (metal\$3 or wiring or conductive) same pattern) and ((remov\$3 or strip\$4) same (polymer\$3 or photoresist or resist) same pattern) and (metal\$3 or conductive or wir\$3)	US-PPGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB
8	113	((substrate or wafer) same (polyimide or polyamic) same (expos\$ or imaging or irradiat\$4 or illuminat\$4) same develop\$4 same pattern\$4) and ((dielectric or TiO or TiN or SiN) same first) and ((dielectric or TiN or SiN or TiO) same second) and ((remov\$3 or strip\$4) same (polymer\$3 or photoresist or resist) same pattern) and (metal\$3 or conductive or wir\$3)	US-PPGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
9	111	((substrate or wafer) same (polyimide or polyamic) same (expos\$ or imaging or irradiat\$4 or illuminat\$4) same develop\$4 same pattern\$4) and ((dielectric US-PGPUB; USPAT; or TiO or TiN or SiN) same first) USOCR; EPO; JPO; and ((dielectric or TiN or SiN or DERWENT; IBM_TDB TiO) same second) and ((remov\$3 or strip\$4) same (polyamic or polyimide) same pattern) and (metal\$3 or conductive or wir\$3)	